Docket Number: 081468-0306781 Client Reference: P-0381.010-US

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of

ØERI LOF t al.

**Group Art Unit:** 

Application No.: 10/705,805

**Examiner: Unassigned** 

Filed: November 12, 2003

Confirmation No.: Unassigned

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

## **INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed					
A Table Comment		<b>行。网络</b> 在独特在企业	17.3 A. 1.4 S. 1.5 S.	· "我们是我们是一个一个一个一个一个一个一个一个一个一个一个一个一个一个一个一个一个一个一个					
	Joeri LOF et al.	10/705,783	11/12/2003	<ul> <li>Specification</li> <li>Drawings</li> <li>Other: stamped receipt card</li> </ul>					
	Helmar VAN SANTEN et al.	10/743,271	12/23/2003	<ul><li>☒ Specification</li><li>☒ Drawings</li><li>☒ Other: stamped receipt card</li></ul>					
	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>					
	Klaus SIMON et al.	10/724,402	12/01/2003	<ul> <li>Specification</li> <li>Drawings</li> <li>Other: stamped receipt card</li> </ul>					
	Joannes T. DESMIT et al.	10/705,804	11/12/2003	<ul> <li>Specification</li> <li>Drawings</li> <li>Other: stamped receipt card</li> </ul>					
	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<ul> <li>Specification</li> <li>Drawings</li> <li>Other: stamped receipt card</li> </ul>					
	Amo J. BLEEKER	10/715,116	11/18/2003	<ul> <li>Specification</li> <li>Drawings</li> <li>Other: stamped receipt card</li> </ul>					
	Bob STREEFKERK et al.	10/719,683	11/24/2003	<ul> <li>Specification</li> <li>Drawings</li> <li>Other: stamped receipt card</li> </ul>					
	Joeri LOF et al.	10/705,816	11/12/2003	<ul><li>Specification</li><li>Drawings</li><li>Other: stamped receipt card</li></ul>					

<sup>\*</sup>The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

AR   2004/000627A1   01/01/2004   Karl-Heinz SCHUSTER	FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office FEB 2 0 2004							Atty. Dkt. No.	M#	M#			Client Ref.				
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*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation not in conformance and not considered. Include copy of this form with next communication to Applicant.			Initial if citation c	onsidere	ed, whe	ether or	not citation	n is	in conformar	nce w	ith MPEP § 60	9. Dra	aw li	ne thro	ough	citation	if

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

<u>PLEASE DO NOT PRINT</u> the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE <u>RETURN</u> A COPY OF <u>THIS LETTER</u>** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each enclosed document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

Jean-Paul G. Hoffman Registration Number #2663

Customer Number: 00909

Date: February 20, 2004

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